

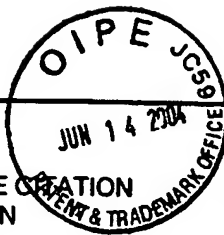
CUSTOMER NO.: 27623

Sheet 1 of 1

FORM PTO-1449

INFORMATION DISCLOSURE
IN AN APPLICATION

(Use several sheets if necessary)



Docket Number (Optional)

637.0033USX

Application Number

10/779,516

Applicant

Udo Dinger et al.

Filing Date

February 13, 2004

Group Art Unit

2878

U. S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
ACH	2001/0028518	10/11/01	Kaiser	359	883	
ACH	2002/0114089	8/22/02	Dinger et al.	359	853	
ACH	D322,813	12/31/91	Wilson	D19	88	
ACH	2,326,059	8/3/43	Nordberg	106	52	
ACH	5,070,045	12/3/91	Comte et al.	501	4	
ACH	5,591,682	1/7/97	Goto	501	4	
ACH	6,198,793	3/6/01	Schultz et al.	378	34	
ACH	6,244,717	6/12/01	Dinger	359	859	
ACH	6,377,655	4/23/02	Murakami et al.	378	84	

FOREIGN PATENT DOCUMENTS

	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						YES	NO
ACH	0 955 565 A2	11/10/99	Europe	—	—	X	
ACH	198 30 449 A1	1/27/00	Germany	—	—		X
ACH	199 03 807 A1	11/11/99	Germany	—	—		X
ACH	199 07 038 A1	8/31/00	Germany	—	—		X
ACH	199 23 609 A1	12/2/99	Germany	—	—		X
ACH	04367538 A	12/18/92	Japan	—	—	X	
ACH	2000247681 A	9/12/00	Japan	—	—	X	

OTHER DOCUMENTS (including Author, Title, Date, Pertinent Pages, Etc.)

ACH	XP-000991487 Mask Substrate Requirements and Development for Extreme Ultraviolet Lithography (EUVL), by Tong et al., and Lawrence Livermore Nat'l Lab., Motorola, and Intel Corp., (9/99), SPIE Vol. 3873, pgs 421-428.
ACH	XP-008012782 Experiences in the Precision Machining of Grazing Incidence X-Ray Mirror Substrates, by McKeown et al., from Cranfield Unit for Precision Engineering and Cranfield Institute of Technology, (1985), SPIE Vol. 571, Large Optics Technology, pgs 42-50
ACH	Mirror Substrates for EUV-Lithography: Progress in Metrology and Optical Fabrication Technology, by Dinger et al., (2000), SPIE Vol. 4146, pgs 35-46

EXAMINER

Allen C. Ho

DATE CONSIDERED

31 Aug 2005

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP §609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.

CUSTOMER NO.: 27623

Sheet 1 of 1

FORM PTO-1449

INFORMATION DISCLOSURE CITATION
IN AN APPLICATION

(Use several sheets if necessary)

Docket Number (Optional)

637.0033USX

Application Number

10/779,516

Applicant

DINGER et al.

Filing Date

February 13, 2004

Group Art Unit

2878

U. S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE

FOREIGN PATENT DOCUMENTS

	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						YES	NO
ACH	WO02099818	12/12/02	WIPO			XXX	

OTHER DOCUMENTS (including Author, Title, Date, Pertinent Pages, Etc.)

ACH	Allen et al. "An Ion Figuring System for Large Optic Fabrication", SPIE Vol. 1168 Current Developments in Optical Engineering and Commercial Optics (1989), pp. 33-50.
ACH	Allen et al. "Demonstration of an Ion Figuring Process", SPIE Vol. 1333 Advanced Optical Manufacturing and Testing (1990), pp. 22-33
ACH	Wilson et al. "Surface Figuring Using Neutral Ion Beams", SPIE Vol. 966 Advances in Fabrication and Metrology for Optics and Large Optics (1988), pp. 74-80.

EXAMINER

Allen C. Ho

DATE CONSIDERED

19 Sep 2005

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP §609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.